





Docket No.: 2328-050

PATENT

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of

Jian CHEN et al

Serial No. 09/821,027

Filed: March 30, 2001

For: INDUCTIVE PLASMA PROCESSOR HAVING COIL WITH PLURAL  
WINDINGS AND METHOD OF CONTROLLING PLASMA DENSITY

Group Art Unit: 1763

Examiner: M. Crowell

HR5  
1/22/02  
M.

AMENDMENT

Assistant Commissioner for Patents  
Washington, D. C. 20231

Sir:

In response to the August 9, 2002 Office Action, please amend  
the referenced application as follows:

IN THE CLAIMS:

Please amend claims 1, 5, 7, 11, 12, 13, 15, 17, 19, 20, 21,  
22, 23, 25, 26 and 28 as follows:

B 1. (amended) A method of controlling the distribution of  
electromagnetic fields launched by an excitation coil to excite a  
plasma in a vacuum plasma processor for processing a workpiece, the  
coil including plural parallel connected windings for coupling  
electromagnetic fields to plasma in the chamber, the method  
comprising varying (a) the total amount of power applied to the  
plural parallel connected windings so that for different  
distributions of electromagnetic fields different amounts of total

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